



Session Title:	[TA1] Advanced Atomic Scale Thin Films III
Session Date:	November 21 (Tue.), 2023
Session Time:	08:30-10:10
Session Room:	Room A (Capri Room, 2F)
Session Chair:	Prof. Woo Hee Kim (Hanyang Univ., Korea)

[TA1-1] [Invited]

08:30-08:50

Effect of Surface Pre-Treatment on the Initial Growth Stages of ALD-Ir Thin Films

Myung Jin Jung and Se Hun Kwon (Pusan Nat'l Univ., Korea)

[TA1-2] [Invited]

08:50-09:10

Spatial Atomic Layer Deposition of Functional Thin Films

Viet Huong Nguyen (Phenikaa Univ., Vietnam)

[TA1-3]

09:10-09:30

Development of Low-K Smart PECVD Equipment and Process for System LSI Devices-II

SM Lee, JY Yang, SW Lee, SH Yeo (TES Co., Ltd., Korea), TJ Choi (Sejong Univ., Korea), JK Lee (Pusan Nat'l Univ., Korea), JO Kim (KRISS, Korea), and HJ Jang (TES Co., Ltd., Korea)